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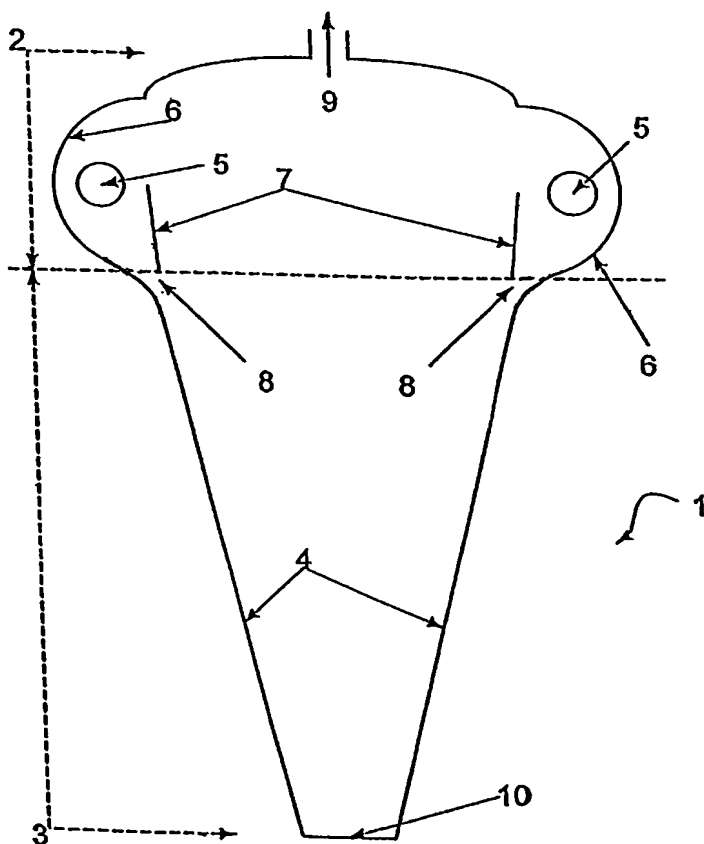
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(54) Title: **AN IMPROVED FLUID TREATMENT SYSTEM**



(57) Abstract: According to one aspect of the present invention there is provided an improved fluid treatment system, including a low-pressure source, where the low-pressure source imparts a low pressure to at least part of the internal volume of the improved fluid treatment system, and at least one fluid inlet (5), and a primary chamber (2), wherein the primary chamber (2) contains at least one baffle (7) adapted to control the flowrate of fluid out of the primary chamber (2), and, a secondary chamber (3), wherein the secondary chamber (3) defines at least one inclined surface (4), and at least one fluid outlet (10), characterised in that, fluid entering from the fluid inlet (5) is pooled between the primary chamber (2) wall and the baffle (7) before flowing out of the primary chamber (2) past the baffle (7) to form a thin film laminar flow on at least part of the surface of the secondary chamber (3) to remove at least part of the gas entrained within the fluid.



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